

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	16	("4410168" "4051010" "4752025" "4818838" "4972990" "5173338" "5474958" "6264185").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:24
S2	0	S1 and (electrochemical near2 machin\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 14:51
S3	0	S1 and ((electrolytic electrolytically) near2 machin\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 14:51
S4	3277	(electrochemical near2 machin\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 15:36
S5	15	(electrochemical near2 machin\$3) and 204/242.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 14:57
S6	5	(electrochemical near2 machin\$3) and 204/242.ccls. and ((negative adj pressure) (vacuum))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 14:58
S7	5	(electrochemical near2 machin\$3) and 204/242.ccls. and ((negative adj pressure) (vacuum)) and (lift remove separate move)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 19:02
S8	1	(electrochemical near2 machin\$3) and 204/242.ccls. and ((negative adj pressure) (vacuum)) and (lift remove separate move) and (piston)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 15:00

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S9	22	(electrochemical near2 machin\$3) and ((negative adj pressure) (vacuum)) and (lift remove separate move) and (piston)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/26 09:56
S10	284	(electrochemical near2 machin\$3) and ((negative adj pressure) (vacuum))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 15:07
S11	221	(electrochemical near2 machin\$3) and ((negative adj pressure) (vacuum)) and @ad<"20031222"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 15:08
S12	172	(electrochemical near2 machin\$3) and ((negative adj pressure) (vacuum)) and @ad<"20031222" and (lift move remove separate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 15:08
S13	5	(electrochemical near2 machin\$3) and ((negative adj pressure) (vacuum)) and @ad<"20031222" and (lift move remove separate) and (positive adj pressure)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 15:55
S14	3	((electrochemical electrochemically electropolish\$2) near2 (machin\$3 polish\$3)) and ((negative adj pressure) (vacuum)) and @ad<"20031222" and (lift move remove separate) and (positive adj pressure) and (electrode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 16:13
S15	1	((electrochemical electrochemically electropolish\$2) near2 (machin\$3 polish\$3)) and ((negative adj pressure) (vacuum)) and @ad<"20031222" and (lift move remove separate) and (positive adj pressure) and (electrode) and ((workpiece substrate) adj holder)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/26 10:08

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S16	1	((electrochemical electrochemically electropolish\$2) near2 (machin\$3 polish\$3)) and ((negative adj pressure) (vacuum)) and @ad<"20031222" and (lift move remove separate detach) and (positive adj pressure) and (electrode) and ((workpiece substrate) adj holder)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 16:23
S17	1265	(substrate workpiece) same (vacuum adj seal)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 16:22
S18	1	((electrochemical electrochemically electropolish\$2) near2 (machin\$3 polish\$3)) and S17	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 16:23
S19	1	S1 and electrode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 16:49
S20	1986	(electrochemical near2 machin\$3) and @ad<"20031222"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:37
S21	736	(electrochemical near2 machin\$3).ti. and @ad<"20031222"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:39
S22	0	(electrochemical near2 machin\$3).ti. and @ad<"20031222" and ((create produce sustain maintain) with (vacuum suction (negative adj pressure)) with (seal\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:41
S23	0	(electrochemical near2 machin\$3).ti. and @ad<"20031222" and ((create produce sustain maintain) same (vacuum suction (negative adj pressure)) same (seal\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:42

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S24	2	(electrochemical near2 machin\$3).ti. and @ad<"20031222" and ((create produce sustain maintain) and (vacuum suction (negative adj pressure)) and (seal\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:42
S25	24	(electrochemical near2 machin\$3).ti. and @ad<"20031222" and (vacuum suction (negative adj pressure))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:48
S26	8802	(vacuum adj chuck)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:48
S27	15	(vacuum adj chuck) and ((electrochemical adj machin\$3) (ECM))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:56
S28	4	(vacuum adj chuck) and ((electrochemical adj machin\$3) (ECM)) and ((substrate workpiece) adj holder)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/21 17:56
S29	17	204/297.03.ccls. and (semiconductor wafer microelectronic microfeature)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/22 10:12
S31	0	204/297.03.ccls. and (semiconductor wafer microelectronic microfeature) and piston	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/22 10:12
S32	5	204/297.03.ccls. and (semiconductor wafer microelectronic microfeature) and lift	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/26 10:10

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S33	2	204/297.03.ccls. and (semiconductor wafer microelectronic microfeature) and (positive adj pressure)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/22 10:50
S34	29	204/297.03.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 15:35
S35	3719	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:28
S36	8	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (vacuum adj chuck)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/26 10:11
S37	316	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (vacuum)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 15:42
S38	2172	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and @ad<"20030121"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 15:43
S39	4	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and @ad<"20030121" and (vacuum adj chuck)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 17:07
S41	124	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and @ad<"20030121" and (machining adj gap)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 15:49

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S42	17	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and @ad<"20030121" and (machining adj gap) and (surface near2 roughness)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:18
S43	0	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and @ad<"20030121" and (machining adj gap) and (degree near parallel\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:19
S44	2	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and @ad<"20030121" and (degree near parallel\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/26 10:17
S45	5	("4410168" "4051010" "4752025" "4818838" "4972990" "5173338" "5474958" "6264185").PN. and (parallel)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:24
S46	820	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and parallel	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:28
S47	826	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and parallel\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:28
S48	18	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and parallelism	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:36
S49	820	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and parallel	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:38

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S50	25	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (resist\$4 near4 (anod\$4 (anod\$2 near2 (corrod\$2 corrosion))))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:40
S51	8	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (resist\$4 near4 (anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) and titanium	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:40
S52	12	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (resist\$4 near4 (anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) and (titanium ti)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:43
S53	177	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) and (titanium ti)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:44
S54	10	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (((anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) near4 (titanium ti))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:45
S55	2	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (((anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) near4 (workpiece adj holder))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:46
S56	0	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((resistant resistance) near3 ((anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) near4 (workpiece adj holder))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:47
S57	0	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((resistant resistance) near3 ((anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) near4 ((workpiece substrate wafer) adj holder))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:47

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S58	0	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((resistant resistance resists) near3 ((anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) near4 ((workpiece substrate wafer) adj holder))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:48
S59	0	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((resistant resistance resist) near3 ((anod\$4 (anod\$2 near2 (corrod\$2 corrosion)))) near4 ((workpiece substrate wafer) adj holder))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:48
S60	1	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (titanium ti) near4 ((workpiece substrate wafer) adj holder)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:49
S61	523	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (titanium ti)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:50
S62	2	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((titanium ti) with holder)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:49
S63	64	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((titanium ti) and (corrosion near2 resist\$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:54
S64	21	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((titanium ti) with (corrosion near2 resist\$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 16:58
S65	2	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((titanium ti) with ((anode anodic) near2 corrosion))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 18:55

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S66	3	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (resist\$4 near4 ((anode anodic) near2 corrosion))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 17:01
S67	0	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and ((resist\$4 near2 corrosion) with platen)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 17:02
S68	1	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (Ti with platen)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 17:03
S69	13	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (titanium with platen)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 17:03
S70	41	(vacuum adj chuck) same (roughness)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/23 17:08
S71	11	(electrochemical near2 machin\$3) and ((negative adj pressure) (vacuum)) and (lift remove separate move) and (piston) and @ad<"20030121"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/26 09:58
S72	4	((electrochemical electrochemically electro-chemical electro-chemically) near2 machin\$3) and (vacuum adj chuck) and @ad<"20030121"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/26 10:12
S73	3280	(electrochemical near2 machin\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/28 11:30

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S74	2	S73 and (resist with anod\$2 with corrosion)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/28 11:31
S75	19	S73 and (anod\$2 with corrosion)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/28 11:32
S76	3964	(resist\$4 with anod\$2 with corrosion)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/28 11:32
S77	939	(resist\$4 with anod\$2 with corrosion) and "204".clas.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/28 11:32
S78	2	"5556327".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/28 18:22
S79	2	"5870271".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/28 18:23
S80	24	("4410168" "4051010" "4752025" "4818838" "4972990" "5556327" "5870271" "5173338" "5474958" "6264185" "6416647" "6743349").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/15 15:24
S81	42338	((plenum (vacuum near (chamber plenum reservoir volume container space holding))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 19:02

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S82	8	((plenum (vacuum near (chamber plenum reservoir volume container space holding))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar)) and (204/242,280.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 19:20
S83	9	((plenum (vacuum near (chamber plenum reservoir volume container space holding))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar eject eject\$3 pin)) and (204/242,280.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 19:23
S84	11	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar eject eject\$3 pin)) and (204/242,280.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 20:31
S85	2045	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar eject eject\$3 pin)) and (vacuum adj chuck) and (workpiece semiconductor microelectronic wafer substrate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 20:34
S86	527	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar eject eject\$3 pin)) and (vacuum adj chuck) and (workpiece semiconductor microelectronic wafer substrate) and (electrode anode cathode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/19 20:35
S87	105	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar eject eject\$3 pin)) and ((vacuum adj chuck).ti. (vacuum adj chuck).clm. (vacuum adj chuck).ab.) and (workpiece semiconductor microelectronic wafer substrate) and (electrode anode cathode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 06:54
S88	1698	269/21.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 06:56

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S89	204	269/21.ccls. and ((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar eject eject\$3 pin))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 07:58
S90	14	269/21.ccls. and ((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston lift\$3 separat\$3 mount mount\$3 actuat\$3 rod bar eject eject\$3 pin)) and (electrode anode cathode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 08:12
S91	223	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston)) and (electrode anode cathode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 08:14
S92	6	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston)) and (electrode anode cathode) and ((vacuum adj chuck).ti. (vacuum adj chuck).ab. (vacuum adj chuck).clm.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 08:15
S93	1	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) with (piston)) same (electrode anode cathode) and ((vacuum adj chuck).ti. (vacuum adj chuck).ab. (vacuum adj chuck).clm.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 08:15
S94	12	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) same (piston)) and (electrode anode cathode) and ((vacuum adj chuck).ti. (vacuum adj chuck).ab. (vacuum adj chuck).clm.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 08:16
S95	41	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) same (piston)) and (electrode anode cathode) and ((vacuum adj chuck))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 08:18

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S96	42	((plenum (vacuum near (chamber plenum reservoir volume container space holding chuck))) same (piston) and (electrode anode cathode) and ((vacuum adj chuck) (vacuum near2 workholder))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 08:18
S99	1	269/21.ccls. and (vacuum adj chuck) and (reflectance transmittance) and (water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 10:50
S10 2	8	269/21.ccls. and (vacuum adj chuck) and (reflectance transmittance optical) and ((clean clean\$3) with (surface wafer substrate))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:07
S10 4	991	(269/21.ccls. (vacuum adj chuck)) and (reflectance transmittance optical) and ((clean clean\$3) with (surface wafer substrate))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:11
S10 5	178	(269/21.ccls. (vacuum adj chuck)) and (reflectance transmittance optical) and ((clean clean\$3) with (surface wafer substrate) with water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:11
S10 6	20	(269/21.ccls. (vacuum adj chuck)) and (reflectance transmittance spectroscopic) and ((clean clean\$3) with (surface wafer substrate) with water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:14
S10 7	21	(269/21.ccls. (vacuum adj chuck) 356/244.ccls.) and (reflectance transmittance spectroscopic) and ((clean clean\$3) with (surface wafer substrate) with water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:15
S10 8	1	(356/244.ccls.) and (reflectance transmittance spectroscopic) and ((clean clean\$3) with (surface wafer substrate) with water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:19

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S10 9	3	(356/244.ccls.) and (reflectance transmittance spectroscopic) and ((clean clean\$3 rinse rins\$3) with (surface wafer substrate) with water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:21
S11 0	3	(356/244.ccls.) and (spectrophotometer) and ((clean clean\$3 rinse rins\$3) with (surface wafer substrate) with water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:29
S11 1	29	("356".clas.) and (spectrophotometer) and ((clean clean\$3 rinse rins\$3) with (surface wafer substrate) with water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/20 11:30